

**EAST Search History****EAST Search History (Prior Art)**

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
S1	1	("6506260").PN.	USPAT; USOCR	OR	OFF	2009/12/01 10:03
S2	1	("6306224").PN.	USPAT; USOCR	OR	OFF	2009/12/01 10:04
S3	1	("6015462").PN.	USPAT; USOCR	OR	OFF	2009/12/01 12:09
S4	1	("20080233760").PN.	US-PGPUB; USPAT	OR	OFF	2009/12/01 13:15

**EAST Search History (Interference)**

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	0	(Frank-Delahaye\$).in.	US-PGPUB; USPAT; UPAD	OR	OFF	2011/01/21 11:32
L2	12159	438/745-753;134/1.3,1,15,34,42,902. ocls.	US-PGPUB; USPAT; UPAD	OR	OFF	2011/01/21 11:34
L3	14	L2 and (wet-chemical adj treatment)	US-PGPUB; USPAT; UPAD	OR	OFF	2011/01/21 11:34
L4	3	L3 and (silicon adj wafer)	US-PGPUB; USPAT; UPAD	OR	OFF	2011/01/21 11:35
S5	0	(wet-chemical adj treatment near20 silicon adj wafer near5 (liquid adj bath) near10 conveyer near10 top adj side near5 (above adj liquid) near20 miniscus near5 edges near5 wafer).clm.	US-PGPUB; USPAT; UPAD	OR	OFF	2011/01/21 10:29

**1/21/2011 11:37:44 AM****C:\Documents and Settings\mangadi\My Documents\EAST\Workspaces\Process for the treatment of substrates, 10599208.wsp**